I. Number	Bits	Search Text	DB	Time stamp
L Number	Hits 22	((((())) as on time ()) as of the () as of t	DB USPAT; US-PGPUB; EPO; JEO; IEM_TOB	Time stamp 2004/05/21 10:01
		configurats3) or aperture or [wavelength or coherenc5] or illumina84 or focus or defocus) same (expos33 or radia54 or irradia84 or light or illumina54)))) and (resist or photoresist) and phase add shift53 same [mask or photomask or		
2	9	reticle) ((full adj phase adj shift\$3 or full adj phase) adj (mask or reticle or photomask)) not ((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5,ccls.)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21 10:03
3	7		USPAT; US-PGPUB; EPO; JPO; IBM TDB	2004/05/21 10:0
4	525	(1430/5,211-212.39,396.07.35/53,77 [(1430/5,211-212.39,396.396.07.35/53,77 [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.168.07.90) [(1450/5,211-212.396.07	USPAT: US-PCPUB; EPO; JPO; IBM_TDB	2004/05/21 10:0:

5	46	((((()))mase add) shift33 same (mask or potentials) are (citized) states ((citized)) stat	USEAT: US-PEFUB; EPO; JPO; IEM_TDB	2004/05/21 10:07
6		((((()))) amp ()	USPAT; US-ECPUB; EPO; JPO; IBM_TOB	2004/05/21 10:07
-	1815	(phase adj shift\$3 same (mask or photomask or reticle)) same (resist or photoresist or photosensit\$4)	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/04/30 14:30
-	798	((phase add shift3) same (mask or photomask or reticle)) same (resist or photomask or photomask or reticle) near) or ((mask or photomask or reticle) near) set) or (second or complementary) add (mask or photomask or reticle) or overla55)	USPĀT; US-PGPUB; EPO; JPO; 1BM_TDB	2003/04/28 16:37
-	126	((fphase adj shift33 same (mask or photomask or reticle)) same (resist or photomask or reticle) same (resist or photomesist or photosensit\$4) and (trim or (mask or photomask or reticle) near3 set) or (second or complementary) adj (mask or photomask or reticle) or overla\$51) and (transistor near3 gate or qate adj shr7nk\$3)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:25
-	97	((([phase ad] bhift%] same (mask or photorask or reticle)) same (resist or photoresist or photosensit%)) and (trim or ([mask or photomask or reticle) near3 set) or (second or complementary) add) (mask or photomask or reticle) or overlas(5)) and (transistor near3 gate or overlas(5)) and (tresolution or resolution)	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2003/04/28 16:25

		[[[[[]]]]] ame unit particular) amen unask or photomask or retailed) amen (resist or photomask or retailed) amen particular) amen particular a	USPAT; US-PGPUB; EPO; JPO; IBM_TD9	2003/04/28 16:26
-		((((()))) make ady shirt(3) same (mask or photomask or reticle)) same (result of the photomask or reticle) man (result of the photomask or reticle) near) or ((mask or photomask or reticle) near) or ((mask or photomask or reticle) near) or ((mask or photomask or reticle) near) over((a5)) and ((transitor near) gate or over((a5))) and ((pattern or pattern or resolvi))) and (optical ad) ((massetor or retorive))) and (optical ad) ((massetor or coherence)) or ((liminask or focus or defocus) mass ((mapped)) or redshift (or (does or does)) and ((does or does)) or intensity)) and	US-PGPUB; EPO; JPO; IBM_TDB	2004/02/13 11:14
-	24	((((()))mase add shifted) same (mask or photomask or recicial) same (related or the control of t	USPAT; US-PGPUB; EFO; JFO; IBM_TDB	2004/02/13 11:15
		overlas5)) and (transistor near3 gate or gate adj shrink\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or configurat3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or irradia\$4 or light or illumina\$4)) and (dose or dosage or intensity)		
-	2	(("20020187636") or ("20020197543")).PN.	USPAT; US-PGPUB; EPO; JPO; IBM TDB	2003/04/28 16:33
-	22	[1"628419") or ("6519501") or ("620900768419") or ("62000076829") or ("653187") or ("653187") or ("653187") or ("6531889") or ("653666") or ("653689") or ("653689") or ("6536891") or ("6536891") or ("6537395") or ("65373595") or ("6537395") or ("	USPAT; US-PCPUB; EPO; JPO; IBM_TOB	2003/04/28 16:34

-	21	(((("20020187636") or ("20020197543")).PN.) or ((("6284419") or	USPAT; US-PGPUB	2003/04/28 16:35
		("6519501") or ("20020076622") or	03-10108	
		("6453457") or ("6337172") or ("6541165")		
		or ("6503666") or ("6162568") or		
		("6255024") or ("6268091") or ("6319644")		
		or ("6421111") or ("5972569") or ("5405721") or ("6042973") or ("6127096")		
		or ("6374396") or ("6096457") or		
		("6106979") or ("6040892") or ("6120952")		
		or ("5741624")).PN.)) not (((((phase adj	i	
		shift\$3 same (mask or photomask or		
		reticle)) same (resist or photoresist or		
		photosensit\$4)) and (trim or ((mask or	1	
		photomask or reticle) near3 set) or		
		(second or complementary) adj (mask or photomask or reticle) or overlas5)) and		
		(transistor near3 gate or gate ad)		
	i	shr?nk\$31) and (resolution or resolv\$3))		
		and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
	1	or coherenc@1 or illumina@4 or focus or	1	
	1	defocus) same (expos\$3 or radia\$4 or		
	398	irradia\$4 or light or illumina\$4))) ((430/5,311-312,319,394,396 or 355/53,77	USPAT:	2004/02/13 11:17
-	398	or 378/34-35 or 716/19-21).ccls. and	US-PGPUB;	2004/02/13 11:1/
	1	(phase adj shift\$3 same (mask or photomask	EPO; JPO;	
		or reticle)) same (trim or ((mask or	IBM TDB	
		photomask or reticle) near3 set) or		
		(second or complementary) adj (mask or		
		photomask or reticle) or overlas5)) not ((((((phase ad) shift\$3 same (mask or		
		photomask or reticle)) same (resist or		
		photoresist or photosensit\$4)) and (trim		
		or ((mask or photomask or reticle) near3		
		set) or (second or complementary) adj		
		(mask or photomask or reticle) or		
		overla85)) and (transistor near3 gate or		
		gate adj shr?nk\$3)) and (resolution or resolv\$3)) and (optical adj (parameter or		
		configurat\$3) or aperture or (wavelength		
		or coherenc\$1 or illumina\$4 or focus or		
		defocus) same (expos\$3 or radia\$4 or	Į.	
		irradia\$4 or light or illumina\$4)))	1	
-	4	(("5885734") or ("6077630") or	USPAT;	2003/04/28 18:09
	40	("20010000240") or ("20010028985")).PN. (("4037918") or ("4456371") or ("5302477")	US-PGPUB USPAT:	2003/04/30 14:58
	48	or ("5308741") or ("5316878") or	US-PGPUB	2003/04/30 14:30
		("5324600") or ("5328807") or ("5334542")	1 - 2 - 2 - 2 - 2	
		or ("5352550") or ("5364716") or	1	
		("5424154") or ("5480746") or ("5496666")	1	
		or ("5498579") or ("5503951") or	1	
		("5523186") or ("5527645") or ("5532090")		
		or ("5537648") or ("5538815") or ("5539568") or ("5565286") or ("5573890")	1	
		or ("5595843") or ("5620816") or	1	
		("5635316") or ("5636131") or ("5702848")	1	
		or ("5725969") or ("5761075") or		
		("5766804") or ("5766806") or ("5807649")		
		or ("5827623") or ("5858580") or		
		("5885734") or ("5923566") or ("5994002") or ("5998068") or ("6004702") or		
		("6010807") or ("6057063") or ("6066180")		
		or ("6077630") or ("6083275") or		
		("6228539") or ("6251549") or	1	
		("6258493")).PN.		
	9	(("5472814") or ("5923562") or ("6130012")	USPAT;	2003/04/30 15:02
		or ("6139994") or ("6185727") or	US-PGPUB	
		("6335128") or ("6338922") or	1	
		("20010000240") or ("20010028985")).PN.	1	

	12	(("6420074") or ("6436590") or	USPAT;	2003/04/30	15:06
		("20020083410") or ("20020122994") or ("20020127479") or ("20020129327") or	US-PGPUB		
		("20020127479") or ("20020129327") or ("20020136964") or ("20020142231") or			
		("20020142232") or ("20020144232") or			
		("20020152454") or ("20020155363")).PN.		0004/00/110	
	6	((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or	USPAT; US-PGPUB;	2004/02/13	11:17
		photomask) same (resist or photoresist))	EPO; JPO;		
		and 430/5.ccls.	IBM TDB		
	1	("6524752").PN.	USPAT; US-PGPUB	2003/05/08	16:46
	4	((full adj phase adj shift\$3 or full adj	USPAT;	2004/02/13	11:18
	,	phase) adm (mask or reticle or photomask))	US-PGPUB;		
		not (((full or complete or overall) adj	EPO; JPO;		
		phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist))	IBM_TDB		
		and 430/5,ccls.)			
	357	((dose or dosing or dosage or intensity)	USPAT;	2003/05/13	18:49
		same [second ad] [mask or photomask or	US-PGPUB;		
		reticle()) not (((430/5,311-312,319,394,396 or 355/53,77	EPO; JPO; IBM TDB		
		or 378/34-35 or 716/19-21).ccls. and			
1		(phase adj shift\$3 same (mask or photomask			
		or reticle)) same (trim or ((mask or photomask or reticle) near3 set) or			
		(second or complementary) add (mask or	(
		photomask or reticle) or overla\$5)) not	1		
		((((((phase ad) shift\$3 same (mask or			
		photomask or reticle)) same (resist or photoresist or photosensit\$4)) and (trim			
		or ((mask or photomask or reticle) near3			
1		set) or (second or complementary) adj			
		(mask or photomask or reticle) or overlas5)) and (transistor near) gate or			
		gate adi shr?nk\$3)) and (resolution or			
		resolv\$3)) and (optical adj (parameter or			
		configurat\$3) or aperture or (wavelength			
		or coherenc%1 or illumina%4 or focus or defocus) same (expos%3 or radia%4 or			
		irradia\$4 or light or illumine\$4))))			
	16	(((dose or dosing or dosage or intensity)	USPAT;	2004/05/21	10:09
		same (second ad) (mask or photomask or	US-PGPUB; EPO; JPO;		
		reticle))) not (((430/5,311-312,319,394,396 or 355/53,77	IBM TDB		
		or 378/34-35 or 716/19-21).ccls. and			
		(phase adj shift\$3 same (mask or photomask			
		or reticle)) same (trim or ((mask or photomask or reticle) near3 set) or			
		(second or complementary) adj (mask or		1	
		photomask or reticle) or overla\$5)) not	1.		
		((((((phase adj shift\$3 same (mask or photomask or reticle)) same (resist or			
		photomask or recicle); same (resist or photoresist or photosensit\$4)) and (trim			
		or ((mask or photomask or reticle) near3			
		set) or (second or complementary) adj			
		(mask or photomask or reticle) or overlas5)) and (transistor near3 gate or			
		gate adj shr?nk\$3)) and (resolution or			
		resolv\$3)) and (optical adj (parameter or			
		configurat\$3) or aperture or (wavelength			
		configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or			
		configurat\$3) or aperture or (wavelength			
		configurat\$3) or aperture or (wavelength or coherenc\$1 or illumina\$4 or focus or defocus) same (expos\$3 or radia\$4 or			

-	92	((((()))) asset (())) asset (())) asset (())) between the (()) asset (()) asset (()) asset (())) asset (()) asset (())) asset (()) a	US-PGPUB; US-PGPUB; SPO; JPO; IBM_TOB	2004/05/21	10:07
=	37	I(I() (puase adj shift(3) asset (mask or photocask) or reliciol) asset (resist or photocask) or reliciol) asset (resist or photocask) or reliciol) asset (resist or photocask) or resist (resist) or (asset of or complementary) add (sask) or photocask or reticle) or gaple add) shift(3) and (resolution or resolvi3)) and (optical add) (parameter or resolvi3)) and (optical add) (parameter or coherents) or liluminaté or forcis or defectus) same (seposit) or radialé or tratfalés or tratfal	USPAT; US-PGPUB; EPO, JPO; IBM_TDB	2004/05/21	10:06
-	495	photocasks or reticiel) same (resist or photocasks or reticiel) same (resist or photocasks) and (trim see that the second	USPAT)	2004/05/21	10:04
		(phase add) shift(3) amm (mask or photomask) or reficiely amme (tran or (mask or reficiely) amme (tran or (mask or reficiely) amme (tran or (mask or photomask) or traited) and or translation of the control of the con	EPO; JPO; IBM_TDB		
-	7	irradia\$4 or light or illumina\$4))) ((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or	USPAT; US-PGPUB; EPO; JPO;	2004/05/21	10:03
-	8	photomask) same (resist or photoresist)) and 430/5.ccls. ((full adj phase adj shift\$3 or full adj phase) adj (mask or reticle or photomask)) not ((full or complete or overall) adj phase adj shift\$3 adj (mask or reticle or photomask) same (resist or photoresist)) and 430/5.ccls.)	IBM_TDB USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21	10:03
Search His	toru r	/21/04 10:28:10 AM Page 6			
search His	itory 5,	21/04 10:20:10 MM Lade P			

- 20	[1(Gose or dozing or dozage or intensity] same (second sc) most or photomask or [1(GOS) 10-12, 13, 19, 19, 19 or 535/53, 77 or 387/3-33 or 18/3-21) cclls end or reticle) sement(rin or (incommank or reticle) sement(rin or incommank or reticle) reticle) reticle (incommank or reticle) reticle (incommank or reticle) reticle (incommank or reticle) reticle (incommank or reticle) or	USPAT; US-PGPUB; EPO; JPO; IBM_TDB	2004/05/21	10:00
	(mask or photomask or redicie) of coverlado), and translator neals gate or gate and shrinked marked parts and shrinked parts an			